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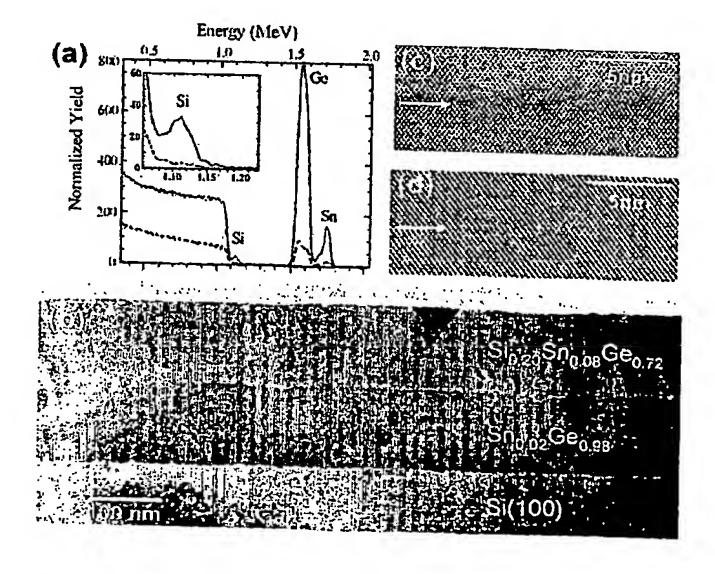
- (71) Applicant (for all designated States except US): ARI-ZONA BOARD OF REGENTS, acting for and on behalf of ARIZONA STATE UNIVERSITY [US/US]; Brickyard Suite 601, Room 691AA, 699 S. Mill Ave., Tempe, AZ 85281 (US).
- (72) Inventors; and

(75) Inventors/Applicants (for US only): KOUVETAKIS, John [US/US]; 7032 E. Indigo, Mesa, AZ 85207 (US). BAUER, Matthew [US/US]; 1996 E. Rice Drive, Tempe, AZ 85283 (US). TOLLE, John [US/US]; 1489 S. Dave Street, Gilbert, AZ 85233 (US).

- (74) Agent: ONEY, Richard, E.; Tiffany & Bosco, P.A., Camelback Esplanade II, 2525 East Camelback Road, Third Floor, Phoenix, AZ 85016-4237 (US).
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(54) Title: SI<sub>x</sub>SN<sub>y</sub>GE<sub>1-x-y</sub> AND RELATED ALLOY HETEROSTRUCTURES BASED ON SI, GE AND SN



(57) Abstract: A novel method for synthesizing device-quality alloys and ordered phases in a Si-Ge-Sn system uses a UHV-CVD process and reactions of SnD<sub>4</sub> with SiH<sub>3</sub>GeH<sub>3</sub>. Using the method, single-phase Si<sub>x</sub>Sn<sub>y</sub>Ge<sub>1-x-y</sub> semiconductors ( $x \le 0.25$ ,  $y \le 0.11$ ) are grown on Si via Ge<sub>1-x</sub>Sn<sub>x</sub> buffer layers The Ge<sub>1-x</sub>Sn<sub>x</sub> buffer layers facilitate heteroepitaxial growth of the Si<sub>x</sub>Sn<sub>y</sub>Ge<sub>1-x-y</sub> films and act as compliant templates that can conform structurally and absorb the differential strain imposed by the more rigid Si and Si-Ge-Sn materials. The SiH<sub>3</sub>GeH<sub>3</sub> species was prepared using a new and high yield method that provided high purity semiconductor grade

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